



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Katsutoshi Izumi et al

Group Art Unit: 2813

Serial No.: 10/802,806

Examiner: Heather Anne Doty

Filed: March 18, 2004

P.T.O. Confirmation No.: 5100

For: MANUFACTURING METHOD FOR BURIED INSULATING LAYER-TYPE  
SEMICONDUCTOR SILICON CARBIDE SUBSTRATE

**AMENDMENT IN RESPONSE TO FINAL REJECTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Date: June 14, 2006

Sir:

In response to the Office Action dated February 21, 2006, please amend the above-identified application as set forth below:

Amendments to the Claims begin on page two of this paper.

Remarks begin on page five of this paper.